Approved for use through 10/31/2002, OMB 0651-0031

## **CONTINUED EXAMINATION (RCE)** TRANSMITTAL

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REQUEST	Application Number	09/807,061	
FOR	Filing Date	07/09/2001	_
ONTINUED EXAMINATION (RCE)	First Named Inventor	Christian Kratzsch et al.	
TRANSMITTAL	Art Unit	2853	
Address to: Commissioner for Patents Box RCE Washington, DC 20231	Examiner Name	Blaise L. Mouttet	
	Attorney Docket Number	STUR-35	

This is a Request for Continued Examination (RCE) under 37 CFR 1.114 of the above-identified application. Request for Continued Examination (RCE) practice under 37 CFR 1.114 does not apply to any utility or plant application filed prior to June 8, 1995, or to any design application. See Instruction Sheet for RCEs (not to be submitted to the USPTO) on page 2. Submission required under 37 CFR 1.114 a. Previously submitted Consider the amendment(s)/reply under 37 CFR 1.116 previously filed on \_\_ (Any unentered amendment(s) referred to above will be entered). Consider the arguments in the Appeal Brief or Reply Brief previously filed on iii. 🗌 Other b. Enclosed Amendment/Reply Information Disclosure Statement (IDS) ii. Affidavit(s)/Declaration(s) Other Miscellaneous a. Suspension of action on the above-identified application is requested under 37 CFR 1.103(c) for a period of \_\_\_\_\_ months. (Period of suspension shall not exceed 3 months; Fee under 37 CFR 1.17(i) required) b. | Other Fees The RCE fee under 37 CFR 1.17(e) is required by 37 CFR 1.114 when the RCE is filed. The Director is hereby authorized to charge the following fees, or credit any overpayments, to Deposit Account No. 16-0221 RCE fee required under 37 CFR 1.17(e) 07/14/2004 SBIRETA1 00000125 09807061 Extension of time fee (37 CFR 1.136 and 1.17) iii. 🖊 Other any deficiencies 01 FC:2001 385.00 GP b. Check in the amount of \$ 385.00 c. Payment by credit card (Form PTO-2038 enclosed) WARNING: Information on this form may become public. Credit card information should not be included on this form. Provide credit card information and authorization on PTO-2038. SIGNATURE OF APPLICANT, ATTORNEY, OR AGENT REQUIRED Name (Print IType) Registration No. (Attorney/Agent) 20.570 Signature Date 07/06/2004 CERTIFICATE OF MAILING OR TRANSMISSION I hereby certify that this correspondence is being deposited with the United States Postal Service with sufficient postage as first class mail in an envelope addressed to: BOX RCE. Commissioner for Patents. PO Box 1450. Alexandria, VA 22313-1450 on the date shown below. Scott R. Føster Name (Print/Type) Signature 07/06/2004

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## IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Application of: Christian Kratzsch et al.

Serial No.: 09/807,061

Filing Date: 07/09/2001

For: METHOD FOR SHAPING MATERIALS WITH

PLASMA-INDUCING HIGH-ENERGY RADIATION

Group Art Unit: 2853

Examiner: Blaise L. Mouttet

Attorney's Docket No.: STUR-35

Mail Stop Amendment

Commissioner for Patents

P.O. Box 1450

Alexandria, VA 22313-1450

Sir:

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July 6, 2004

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## AMENDMENT TO THE CLAIMS

Claims 11-21 (canceled).

Claim 22 (new): A method for materials processing by plasmainducing high-energy radiation, the method comprising the steps of: directing plasma-inducing high-energy radiation in a first direction onto a material to be processed and establishing a vapor capillary in the material;

measuring simultaneously instantaneous intensity of the radiation within the vapor capillary in a plane of observation that is oriented transversely to the first direction and determining in the plane of observation spatial shapes of two spaced-apart peak-intensity regions (10,12) of the radiation emitted from the vapor capillary and of a minimum intensity region (11) that is formed between the two peak-intensity regions in the vapor capillary;

comparing the determined spatial shapes of the peakintensity regions with predetermined region shapes; and

controlling a materials processing operation as a function of deviations of the determined shapes from the predetermined region shapes.